

N THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Cho, et al.

Attorney Docket No.: NOVLP089

Patent: 7,265,061 B1

Issued: Sep. 4, 2007

Title: METHOD AND APPARATUS FOR UV EXPOSURE OF LOW DIELECTRIC CONSTANT MATERIALS FOR POROGEN REMOVAL AND IMPROVED MECHANICAL PROPERTIES

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as first-class mail on May 16, 2008 in an envelope addressed to the Commissioner for Patents, P.O. Box 1450

Alexandria, V A 22/313-1450.

Signed:

Quyen Vuona

REQUEST FOR CERTIFICATE OF CORRECTION OF OFFICE MISTAKE

(35 U.S.C. §254, 37 CFR §1.322)

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Attn: Certificate of Correction

Dear Sir:

Attached is Form PTO-1050 (Certificate of Correction) at least one copy of which is suitable for printing. The errors together with the exact page and line number where the errors are shown correctly in the application file are as follows:

COVER PAGE:

1. Add the following section and information:

Certificate

MAY 2 2 2008

of Correction

--Related U.S. Application Data

(60) Provisional application No. 60/469,433, filed on May 9, 2003. --

This appears correctly in the Amendment After Allowance, Before Payment of Issue Fee, filed November 29, 2006, on page 2.

Patentee hereby requests expedited issuance of the Certificate of Correction because the error lies with the Office and because the error is clearly disclosed in the records of the Office. As required for expedited issuance, enclosed is documentation that unequivocally supports the patentee's assertion without needing reference to the patent file wrapper.

It is noted that the above-identified errors were printing errors that apparently occurred during the printing process. Accordingly, it is believed that no fees are due in connection with the filing of this Request for Certificate of Correction. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 50-4480 (Order No. NOVLP089).

Respectfully submitted, WEAVER AUSTIN VILLENEUVE & SAMPSON, LLP

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P.O. Box 70250 Oakland, CA 94612-0250 (510) 663-1100 Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB Control number

(Also Form PT-1050)

UNITED STATES PATENT AND TRADEMARK OFFICE CERTIFICATE OF CORRECTION

PATENT NO. : 7,265,061

Page 1 of 1

DATED

: September 4, 2007

INVENTOR(S): Cho et al.

It is certified that error appears in the above-identified patent and that said Letters Patent are hereby corrected as shown below:

In the Cover Page;

Add the following section and information:

Related U.S Application Data

(60) Provisional application No. 60/469,433, filed on May 9, 2003

MAILING ADDRESS OF SENDER:

Denise S. Bergin WEAVER AUSTIN VILLENEUVE & SAMPSON, LLP P.O. Box 70250 Oakland, CA 94612-0250

PATENT NO. 7,265,061 No. of Additional Copies on

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Amendments to the Specification

Please replace the paragraph beginning on page 1, line 5 with the following amended version of that paragraph

CROSS-REFERENCE TO RELATED APPLICATIONS

This application is a continuation-in-part claiming priority under 35 USC 120 from US Patent Application No. 10/672,311, filed on September 26, 2003, titled "Method of Porogen Removal from Porous Low-k Films Using UV Radiation," by Adrianne Tipton et al., which application is incorporated herein by reference in its entirety for all purposes, and which in turn claims priority under 35 USC 119(e) from U.S. Provisional Application No. 60/469,433, filed on May 3, 2003, also titled "Method of Porogen Removal from Porous Low-k Films Using UV Radiation." This application is also related to US Patent Application No. 10/404,693, filed on March 31, 2003, titled "Method for Forming Porous Films by Porogen Removal Combined with In Situ Surface Modification," by Raashina Humayun et al.; US Patent Application No. 10/672,305, filed on September 26, 2003, titled "Method for Removal of Porogens from Porous Low-k Films Using Supercritical Fluids," by Adrianne Tipton et al.; and to US Patent Application No. 10/295,965 filed November 15, 2002 by Schulberg, et al., and titled "System for Deposition of Mesoporous Materials," which applications are incorporated herein by reference in its entirety for all purposes.

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